

Abstract

Provided is a substrate processing device including a processing bath (12) configured to store processing liquid, and to process a plurality of substrates (24) disposed at predetermined intervals, first and second discharge units (14b₁ and 14b₂) including a flow path (14a) in which the processing liquid flows in a thickness direction of the plurality of substrates (12), a plurality of openings (15) formed along the flow path, and leading end surfaces (16₁ and 16₂) closing a leading end of the flow path (14a), and a supply path (18) that is configured to supply the processing liquid to proximal ends (14b_s and 14b_e) of the first discharge unit (14b₁) and the second discharge unit (14b₂), and includes a supply port (20), and a length from the supply port (20) to the leading end surface (16₂) of the second discharge unit (14b₂) is substantially equal to a length from the supply port (20) to the leading end surface (16₁) of the first discharge unit (14b₁). The substrate processing device can perform processing with higher uniformity among the substrates.